

Appl. No. 10/709,502  
Amdt. dated April 17, 2006  
Reply to Office action of February 02, 2006

**Amendments to the Claims:**

This listing of claims will replace all prior versions, and listings, of claims in the application:

**Listing of Claims:**

- 5 Claim 1 (currently amended): A method for generating a command file of a group of design rule check (DRC) rules for being used by a layout verification tool to verify the a design of an integrated circuit, the method comprising:
- (a) selecting a process from a group of processes;
- (b) setting a set of parameters; and
- 10 (c) extracting program codes from a plurality of modules according to the selected process and the set of parameters so as to generate; and
- (d) combining the program codes extracted from the plurality of modules to form a corresponding command file of the group of DRC rules to be run by the layout verification tool to verify the design of the integrated circuit.
- 15
- Claim 2 (currently amended): The method of claim 1 further comprising:
- [[~~(d)~~]] (e) generating the plurality of modules, the plurality of modules comprising:
- a header module comprising program codes for settings of a verification tool of different processes;
- 20 a variable module comprising program codes for setting fabrication parameters of different processes;

Appl. No. 10/709,502  
Amdt. dated April 17, 2006  
Reply to Office action of February 02, 2006

a layer module comprising program codes for setting layer definitions of  
different processes; and

an operation module comprising program codes of operation definitions of  
different processes.

5 Claim 3 (currently amended): The method of claim 1 wherein the set of parameters  
~~comprise~~ comprises number of metal layers.

Claim 4 (currently amended): The method of claim 1 wherein the set of parameters  
~~comprise~~ comprises number of poly-silicon layers.

10 Claim 5 (currently amended): The method of claim 1 wherein the set of parameters  
~~comprise~~ comprises package parameters.

Claim 6 (currently amended): A method for generating a command file of a group of  
layout versus schematic (LVS) rules and layout parasitic extraction (LPE) rules to be  
used by a layout verification tool to verify ~~the~~ a layout and the parasitic  
characteristics of an integrated circuit, the method comprising:

15 (a) selecting a process from a group of processes;

(b) setting a set of parameters; and

(c) extracting program codes from a plurality of modules according to the selected  
process and the set of parameters ~~so as to generate~~ ; and

20 (d) combining the program codes extracted from the plurality of modules to form a  
corresponding command file of the group of LVS/LPE rules to be run by the  
layout verification tool to verify the layout and parasitic characteristics of the  
integrated circuit.

Appl. No. 10/709,502  
Amdt. dated April 17, 2006  
Reply to Office action of February 02, 2006

Claim 7 (currently amended): The method of claim 6 further comprising:

[[ (d) ] ] (e) generating a plurality of modules, the plurality of modules comprising:

- 5 a header module comprising program codes for settings of a verification tool of different processes;
- a layer module comprising program codes for setting layer definitions of different processes;
- an operation module comprising program codes of operation definitions of different processes; and
- 10 a device module comprising program codes for declaring devices of different processes.

Claim 8 (currently amended): The method of claim 6 wherein the set of parameters ~~comprise~~ comprises number of metal layers.

15

Claim 9 (currently amended): The method of claim 6 wherein the set of parameters ~~comprise~~ comprises number of poly-silicon layers.

Claim 10 (currently amended): The method of claim 6 wherein the set of parameters ~~comprise~~ comprises package parameters.

20

Appl. No. 10/709,502  
Amdt. dated April 17, 2006  
Reply to Office action of February 02, 2006

- Claim 11 (currently amended): A method for generating a command file of a group of design rule check (DRC) rules or layout versus schematic (LVS) rules and layout parasitic extraction (LPE) rules to be used by a layout verification tool to verify the a  
5 layout and the parasitic characteristics of an integrated circuit, the method comprising:
- (a) choosing whether to generate a command file of DRC rules or a command file of LVS/LPE rules;
  - (b) selecting a process from a group of processes;
  - 10 (c) setting a set of parameters; and
  - (d) extracting program codes from a plurality of modules according to the choice in step ~~[[k]]~~ (a), the selected process, and the set of parameters so as to generate a ; and
  - 15 (e) combining the program codes extracted from a plurality of modules to form the command file of DRC rules or the command file of LVS/LPE rules to be run by the layout verification tool.

Claim 12 (currently amended): The method of claim 11 further comprising:

- [[e)] (f) generating a plurality of modules, the plurality of modules comprising:
- 20 a header module comprising program codes for settings of a verification tool of different processes;
  - a variable module comprising program codes for setting fabrication parameters of different processes;

Appl. No. 10/709,502  
Amdt. dated April 17, 2006  
Reply to Office action of February 02, 2006

a layer module comprising program codes for setting layer definitions of  
different processes;

an operation module comprising program codes of operation definitions of  
different processes; and

5 a device module comprising program codes for declaring devices of different  
processes[[:]] .

Claim 13 (currently amended): The method of claim 11 wherein the set of parameters  
~~comprise~~ comprises number of metal layers.

10 Claim 14 (currently amended): The method of claim 11 wherein the set of parameters  
~~comprise~~ comprises number of poly-silicon layers.

Claim 15 (currently amended): The method of claim 11 wherein the set of parameters  
~~comprise~~ comprises package parameters.